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27. The method of claim 1 wherein the resin is treated with a lactate.
28. The method of claim 1 wherein the resin is treated with a hydroxy-containing solvent.
- ²⁹
~~28.~~ The method of claim 1 wherein the resin is treated with an alkane solvent.
- ³⁰
~~29.~~ A method for preparation of a photoresist composition comprising:
- (a) washing a prepared resin with one or more organic solvents, the resin comprising phenolic and alkyl acrylate photoacid labile groups;
 - (b) admixing the treated resin with a photoactive component to provide a photoresist composition.
- ³¹
~~30.~~ The method of claim ³⁰~~29~~ wherein the resin is washed with methylene chloride.
- ³²
~~31.~~ The method of claim ³⁰~~29~~ wherein the resin is washed with a halogenated solvent.
- ³³
~~32.~~ The method of claim ³⁰~~29~~ wherein the resin is washed with a solvent having an ester.
- ³⁴
~~33.~~ The method of claim ³⁰~~29~~ wherein the resin is washed with a lactate.
- ³⁵
~~34.~~ The method of claim ³⁰~~29~~ wherein the resin is treated with a hydroxy-containing solvent.
- ³⁶
~~35.~~ The method of claim ³⁰~~29~~ wherein the resin is treated with an alkane solvent.

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³⁷
~~36.~~ A photoresist composition comprising a photoactive component and a resin comprising phenolic and alkyl acrylate photoacid labile groups, the resin obtainable washing a prepared resin with one or more organic solvents.

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~~37.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is washed with methylene chloride.

³⁷
~~38.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is washed with a halogenated solvent.

³⁷
~~39.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is washed with a solvent having an ester.

³⁷
~~40.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is washed with a lactate.

³⁷
~~41.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is treated with a hydroxy-containing solvent.

³⁷
~~42.~~ The photoresist of claim ³⁷~~36~~ wherein the resin is treated with an alkane solvent.

³⁷
~~43.~~ A substrate having coated thereon a photoresist of claim ³⁷~~36~~.

⁴⁴
~~44.~~ The substrate of claim ⁴⁴~~43~~ wherein the photoresist composition is coated on a microelectronic wafer substrate.

REMARKS

Claim 1 has been amended, claims 13, 14 and 16-24 have been cancelled without prejudice, and claims 25-44 have been added. No new matter has been added by virtue of the